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FORM PTO-1449		US Dept. of Commerce Patent and Trademark Office		ATTORNEY DOCKET NO. ATMI-515		SERIAL NO. 10/015,326	
INFORMATION DISCLOSURE STATEMENT (use several sheets if necessary)				APPLICANT Chongying Xu, et al.		GROUP	
				FILING DATE December 13, 2001		TBA	
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
1/M	AA	5,204,134	4/20/1993	Kirlin, et al.			
	AB	5,536,323	7/16/1996	Kirlin, et al.			
	AC	5,711,816	1/27/1998	Kirlin, et al.			
	AD	6,171,945	1/9/2002	Mandal, et al.			
	AE	4,745,169	5/17/1988	Sugiyama, et al.			
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	AG	6,114,500	9/5/2000	Mori, et al.			
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1/M	AP	5,804,040	9/8/1998	Asai, et al.			
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY	CLASS	SUBCLAS S	TRANSLATION YES NO
							X (abstract only)
1/M	AQ	JP 50-111198	1/28/1974	Japan			X
OTHER DOCUMENTS (Including Author, Title, Journal-Date, Page Number, Etc.)							
1/M	AR	Mantz, et al., "Thermolysis of Polyhedral Oligomeric Silsesquioxane (POSS) Macromers and POSS-Siloxane Copolymers", Chem. Mater., 1996, 8, pg. 1250-1259.					
1/M	AS	Ravi K. Laxman, Neil Hendrix Barry Arkles, Terry A. Tabler "Synthesizing Low-K CVD Materials for Fab Use" Semiconductor International, 11/1/2000					
Continue on Page							
EXAMINER V. Manoharan					DATE CONSIDERED 2/24/03		
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.							



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## OTHER DOCUMENTS (Including Author, Title, Journal-Date, Page Number, Etc.)

<i>W</i>	AT	Alfred Grill, et al., "Novel Low-k Dual-Phase Materials Prepared by PECVD, Mat. Res. Soc. Symp. Proc. Vol. 612, 2000 Materials Research Society
<i>W</i>	AU	Albert Wang, et al. "TMCTS for Gate Dielectric in Thin Film Transistors", Mat. Res. Soc. Meeting 1996
<i>W</i>	AV	A. Grill, et al., "Ultralow-k Dielectrics Prepared by Plasma-enhanced Chemical Vapor Deposition", Applied Physics Letters, Vol. 79, No. 6, Aug. 6, 2001.

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